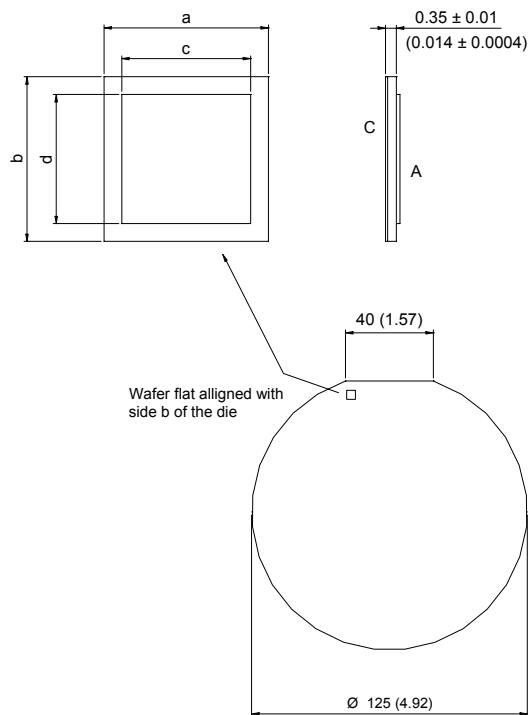


Fred Die in Wafer Form



NOTES:

1. ALL DIMENSIONS ARE SHOWN IN MILLIMETERS (INCHES).

2. CONTROLLING DIMENSION (INCH):

3. DIMENSIONS AND TOLERANCES:

$a = 5.080 \pm 0.05$
 (0.200 ± 0.002)
 $b = 5.08 \pm 0.05$
 (0.200 ± 0.002)
 $c = 4.420 \pm 0.003$
 (0.174 ± 0.0001)
 $d = 4.420 \pm 0.003$
 (0.174 ± 0.0001)

4. LETTER DESIGNATION:

A = Anode (Top Metal)
 C = Cathode (Back Metal)

5. SAWING:

Recommended Blade
 SEMITEC S1025 QS00 Blade

6. MINIMUM ORDER QUANTITY:

300 die

NOT TO SCALE

Electrical Characteristics (Wafer Form)

Parameters	Units	Test Conditions
V_{FM} Maximum Forward Voltage	2.3 V	$T_J = 25^\circ\text{C}$, $I_F = 30\text{ A}$
V_{RRM} Minimum Reverse Breakdown Voltage	600 V	$T_J = 25^\circ\text{C}$, $I_{RRM} = 200\ \mu\text{A}$
I_{RM} Max. Reverse Leakage Current	100 μA	$T_J = 25^\circ\text{C}$, $V_{RRM} = 600\text{ V}$
t_{rr} Typ. Reverse Recovery Time	20 ns	$I_F = 1\text{ A}$, $di/dt = 100\text{ A}/\mu\text{s}$, $V_R = 30\text{ V}$

Mechanical Data

Nominal Back Metal Composition, Thickness	Cr - Ni - Ag (1 KA - 2 KA - 3 KA)
Nominal Front Metal Composition, Thickness	99% Al, 1% Si (3 microns)
Chip Dimensions	0.200" x 0.200" (see drawing)
Reject Ink Dot Size	0.25 mm diameter minimum
Recommended Storage Environment	Storage in original container, in dessicated nitrogen, with no contamination

Ordering Information Table

Device Code	
FD 200 H 06 A 5 B	
① ② ③ ④ ⑤ ⑥ ⑦	
1 - Fred Die	
2 - Chip Dimension in Mils: 200 = 200x200 square	
3 - Process H = HyperFast	
4 - Voltage code V_{rrm} (*100) eg: 06 = 600V	
5 - Chip surface metallization: A = Aluminium (anode), Silver (cathode)	
6 - Wafer diameter in inches	
7 - Packaging: B = Inked Probed Unsawn Wafer (Wafer in box)	